	Application No.	Applicant(s)	
	10/054,621	KRUGER ET AL.	7 N
Notice of Allowability	Examiner	Art Unit	- W -
	Paul D Kim	3729	`
The MAILING DATE of this communication appe All claims being allowable, PROSECUTION ON THE MERITS IS (herewith (or previously mailed), a Notice of Allowance (PTOL-85)	ars on the cover sheet w (OR REMAINS) CLOSED or other appropriate comm	vith the correspondence addressing this application. If not included nunication will be mailed in due cou	rse. THIS
NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIC of the Office or upon petition by the applicant. See 37 CFR 1.313		subject to withdrawal from issue at	the initiative
1. \square This communication is responsive to $9/3/2004$.			
2. The allowed claim(s) is/are <u>1-38</u> .			
3. The drawings filed on 18 January 2002 are accepted by the	Examiner.		
 4. ☐ Acknowledgment is made of a claim for foreign priority unall a) ☐ All b) ☐ Some* c) ☐ None of the: 	der 35 U.S.C. § 119(a)-(d) or (f).	
1. Certified copies of the priority documents have			
2. Certified copies of the priority documents have			
3. Copies of the certified copies of the priority doc	uments have been receiv	ed in this national stage application	from the
International Bureau (PCT Rule 17.2(a)).			
* Certified copies not received:			
Applicant has THREE MONTHS FROM THE "MAILING DATE" of noted below. Failure to timely comply will result in ABANDONMI THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		le a reply complying with the require	ements
5. A SUBSTITUTE OATH OR DECLARATION must be submit INFORMAL PATENT APPLICATION (PTO-152) which give			CE OF
6. CORRECTED DRAWINGS (as "replacement sheets") must	be submitted.		
(a) I including changes required by the Notice of Draftsperso	on's Patent Drawing Revie	ew (PTO-948) attached	
1) ☐ hereto or 2) ☐ to Paper No./Mail Date			
(b) including changes required by the attached Examiner's Paper No./Mail Date	Amendment / Comment of	or in the Office action of	
Identifying indicia such as the application number (see 37 CFR 1.1 each sheet. Replacement sheet(s) should be labeled as such in the			k) of
7. DEPOSIT OF and/or INFORMATION about the depose attached Examiner's comment regarding REQUIREMENT F			the
Attachment(s) 1. ☐ Notice of References Cited (PTO-892)	5. ☐ Notice of I	nformal Patent Application (PTO-15	i2)
2. Notice of Draftperson's Patent Drawing Review (PTO-948)		Summary (PTO-413),	-,
3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/08	Paper No	./Mail Date s Amendment/Comment	
Paper No./Mail Date 4. Examiner's Comment Regarding Requirement for Deposit	8. 🖾 Examiner's	s Statement of Reasons for Allowan	ice
of Biological Material	9. Other		1
		Paul D Kim Examiner Art Unit: 3729	ull

U.S. Patent and Trademark Office PTOL-37 (Rev. 1-04) Application/Control Number: 10/054,621

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DETAILED ACTION

This office action is a response to the amendment filed on 9/3/2004.

Election/Restrictions

1. Since generic claims 1, 19 and 32 are allowable, claims 5-8, 10-18, 27-30 and newly submitted claims 31-38, directed to the making a magnetic head assembly method, previously restricted from the election of species, are now subject to bring rejoined. Claims 1-38 are hereby rejoined and fully examined for patentability under 37 CFR 1.104.

Since all claims previously withdrawn from consideration under 37 CFR 1.142 have been rejoined, the restriction requirement made in the Office action mailed on 3/23/2004 is hereby withdrawn.

Allowable Subject Matter

2. The following is an examiner's statement of reasons for allowance: Upon further consideration with applicant's arguments, examiner agrees with the applicant's counsel that the prior art of record of Ohtomo in view of Lyons fails to disclose the amended claimed invention such as ion beam sputtering a ferromagnetic material layer on the underlying layer and on the side and top surfaces of the shaping layer with the sputtering being directed at an angle to a normal to the flat surface (as per claims 1 and 32) and processes of forming a second photoresist layer with an edge which coincides with an edge site of said pole tip and reactive ion etching the masking layer and the first

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photoresist layer to form the masking layer and the first photoresist layer with said side surface for forming an edge of said pole tip (as per claim 19). Okazawa et al. teach a process for applying silicon oxynitride, which is not a ferromagnetic material, by chemical vapor deposition (CVD), which is not the ion beam sputtering. It is not obvious taken alone or in combination of other references fairly to suggest the claimed invention.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

- 3. Claims 1-38 are allowed.
- 4. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Paul D Kim whose telephone number is 703-308-8356. The examiner can normally be reached on Tuesday-Friday between 8:00 AM to 5:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Peter Vo can be reached on 703-308-1789. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Paul D Kim

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